

TCAD-based Dynamic Thermal X-parameters for PA Self-Heating Analysis Eva Catoggio Supervisor: Prof. S. Donati Guerrieri, Prof. F. Bonani

Research context and motivation

The widespread deployment of **FinFET devices** for advanced digital applications leads to the exploration of this technology for analog high-frequency applications

- $f_T > 200$ GHz in the 22 nm technology node
- Lower cost

The peculiar structure of FinFET devices makes the technology very promising in the view of millimeter-wave phased arrays for 5G/6G.

Dispersion effects in semiconductor devices:

- Trapping phenomena
- Temperature dependence





Multi-finger FinFET structure:

Adopted methodologies

- H_{fin} =25 nm and W_{fin} =14 nm 10 fingers with 30 fins each
- Drain

T-Xpar extraction from TCAD simulations:

- 50 Ω at both input and output ports
- 70 GHz of operating frequency
- HB simulation with 10 harmonics
- Extraction temperatures: [300, 340, 380] K
- Gate bias variation from Class A to Class B

ADS Xpar simulations:

Temp terminal: isolated port representing



Addressed research questions/problems



- the <u>device junction temperature</u> (T_i)
- Class A optimum load on the fundamental

Lumped RC thermal network: coupled to the Xpar model to account for thermal dynamics R_{th} : set to 1 K/µW

C_{th}: sized to have a thermal cutoff of 10 kHz

Self-heating analysis with pulsed input power varying the gate bias from a Class A to a Class B stage.

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Novel contributions

A multi-bias T-Xpar model of a 54 nm Si FinFET is extracted from TCAD LS simulations changing the lattice temperature of the device as an independent parameter. The model is imported into Keysight ADS with fictitious DC voltage ports to set the parameter values, aiming at the simulation of the device with varying operating condition from class A to class B. This is an <u>efficient implementation</u> of a **dynamic thermal model** directly extracted from accurate LS TCAD simulations via T-Xpars.

Submitted and published works

- E. Catoggio et al., "Efficient TCAD Thermal Analysis of Semiconductor Devices", IEEE Trans. El. Dev., vol.68, no.11, 2021, pp.5462-5468.
- E. Catoggio et al., "Efficient TCAD Large-Signal temperature-dependent variability analysis of a FinFET power amplifier", Proc. SISPAD 2021, Dallas (USA), 2021, pp.36-39.
- S. Donati Guerrieri at al., "Bridging the Gap between Physical and Circuit Analysis for Variability-Aware Microwave Design: Modeling Approaches", Electronics, vol.11, no.6, 2022, pp.860-877.
- E. Catoggio et al., "FinFET PAs through temperature-dependent X-parameters extracted from physics-based simulations", Proc. INMMIC 2022, Cardiff (UK), 2022, pp.1-3.
- E. Catoggio et al., "Efficient TCAD Temperature-dependent Large-Signal Simulation of a FinFET Power Amplifier", Proc. EuMIC 2021, 2022, pp.189-192.
- S. Donati Guerrieri et al., "TCAD simulation of microwave circuits: The Doherty amplifier", Solid-State Electronics, vol.197, 2022, pp.108445-108449.
- S. Donati Guerrieri at al., "Bridging the Gap between Physical and Circuit Analysis for Variability-Aware Microwave Design: Power Amplifier Design", Electronics, vol.11, 2022.





Future work

- Simulation of power devices based on GaN: Large-Signal analysis of GaN-based electronic devices to highlight the effect of piezoelectric polarization and traps.
- Simulation of 3D devices: the implementation of a three-dimensional version of the current code in order to simulate 3D structures.

List of attended classes

- 01UJGRV Advanced devices for high frequency applications (27/05/2020, CFU 4)
- 01UAYOQ CAD of semiconductor devices (14/02/2020, CFU 6)
- 02IUGKG II metodo Monte Carlo (04/06/2020, CFU 6)
- 01UIYRV Physics-based modeling of semiconductor devices (01/04/2020, CFU 3)
- 01SFURV Programmazione scientifica avanzata in matlab (25/05/2020, CFU 4)



Electrical, Electronics and

Communications Engineering